

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L16	30024	(trench\$2 recess\$2 via\$1 opening\$1 hole\$1) near10 (polysilicon polycrystalline adj silicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/20 16:28
L17	253	16 same etch\$3 near5 (polysilicon polycrystalline adj silicon) near5 gate adj electrode\$1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/20 16:29
L18	72	17 same source near5 drain	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/20 16:30